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Hako BOTMA  
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For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

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P.O. Box 1450  
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**SUBMISSION OF PRIORITY DOCUMENT**

Attached please find the certified copy of the foreign application from which priority is claimed for this case:

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PILLSBURY WINTHROP LLP  
P.O. Box 10500  
McLean, VA 22102  
Telephone: (703) 905-2000  
Facsimile: (703) 905-2500

Customer Number: 00909

  
\_\_\_\_\_  
Robert C. Perez  
Registration No. 39328

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The attached documents are exact copies of the European patent application described on the following page, as originally filed.

Les documents fixés à cette attestation sont conformes à la version initialement déposée de la demande de brevet européen spécifiée à la page suivante.

**Patentanmeldung Nr.      Patent application No.      Demande de brevet n°**

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Der Präsident des Europäischen Patentamts;  
Im Auftrag

For the President of the European Patent Office

Le Président de l'Office européen des brevets  
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ASML Netherlands B.V.  
De Run 1110  
5503 LA Veldhoven  
PAYS-BAS

Bezeichnung der Erfindung/Title of the invention/Titre de l'invention:  
(Falls die Bezeichnung der Erfindung nicht angegeben ist, siehe Beschreibung.  
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Lithographic apparatus, device manufacturing method, and device manufactured  
thereby

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Title: Lithographic Apparatus, Device Manufacturing Method, and  
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(68)

The present invention relates to a lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation, the radiation system comprising an illuminating system for defining an intensity distribution in a pupil plane, the illuminating system comprising an optical element for deflecting the beam over a range of directions with a direction dependent intensity distribution determined by the optical element;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam from the pupil plane according to a desired pattern;
- a substrate table for holding a substrate; and
- a projection system for projecting the patterned beam onto a target portion of the substrate.

15 The term "patterning means" as here employed should be broadly interpreted as referring to means that can be used to endow an incoming radiation beam with a patterned cross-section, corresponding to a pattern that is to be created in a target portion of the substrate; the term "light valve" can also be used in this context. Generally, the said pattern will correspond to a 20 particular functional layer in a device being created in the target portion, such as an integrated circuit or other device (see below). Examples of such patterning means include:

- A mask. The concept of a mask is well known in lithography, and it includes mask types such as binary, alternating phase-shift, and attenuated 25 phase-shift, as well as various hybrid mask types. Placement of such a mask in the radiation beam causes selective transmission (in the case of a transmissive mask) or reflection (in the case of a reflective mask) of the radiation impinging on the mask, according to the pattern on the mask. In the case of a mask, the

support structure will generally be a mask table, which ensures that the mask can be held at a desired position in the incoming radiation beam, and that it can be moved relative to the beam if so desired;

5 A programmable mirror array. One example of such a device is a matrix-addressable surface having a viscoelastic control layer and a reflective surface. The basic principle behind such an apparatus is that (for example) addressed areas of the reflective surface reflect incident light as diffracted light, whereas unaddressed areas reflect incident light as undiffracted light. Using an appropriate filter, the said undiffracted light can be filtered out of the reflected beam, leaving only the diffracted light behind; in this manner, the beam becomes patterned according to the addressing pattern of the matrix-addressable surface. An alternative embodiment of a programmable mirror array employs a matrix arrangement of tiny mirrors, each of which can be individually tilted about an axis by applying a suitable localized electric field, 10 or by employing piezoelectric actuation means. Once again, the mirrors are matrix-addressable, such that addressed mirrors will reflect an incoming radiation beam in a different direction to unaddressed mirrors; in this manner, the reflected beam is patterned according to the addressing pattern of the matrix-addressable mirrors. The required matrix addressing can be performed 15 using suitable electronic means. In both of the situations described hereabove, the patterning means can comprise one or more programmable mirror arrays. More information on mirror arrays as here referred to can be gleaned, for example, from United States Patents US 5,296,891 and US 5,523,193, and PCT patent applications WO 98/38597 and WO 98/33096, which are 20 incorporated herein by reference. In the case of a programmable mirror array, the said support structure may be embodied as a frame or table, for example, which may be fixed or movable as required; and

25 A programmable LCD array. An example of such a construction is given in United States Patent US 5,229,872, which is incorporated herein by

reference. As above, the support structure in this case may be embodied as a frame or table, for example, which may be fixed or movable as required.

For purposes of simplicity, the rest of this text may, at certain locations, specifically direct itself to examples involving a mask and mask table; 5 however, the general principles discussed in such instances should be seen in the broader context of the patterning means as hereabove set forth.

Lithographic projection apparatus can be used, for example, in the manufacture of integrated circuits (ICs). In such a case, the patterning means may generate a circuit pattern corresponding to an individual layer of the IC, 10 and this pattern can be imaged onto a target portion (e.g. comprising one or more dies) on a substrate (silicon wafer) that has been coated with a layer of radiation-sensitive material (resist). In general, a single wafer will contain a whole network of adjacent target portions that are successively irradiated via the projection system, one at a time. In current apparatus, employing patterning by a mask on a mask table, a distinction can be made between two 15 different types of machine. In one type of lithographic projection apparatus, each target portion is irradiated by exposing the entire mask pattern onto the target portion in one go; such an apparatus is commonly referred to as a wafer stepper or step-and-repeat apparatus. In an alternative apparatus — 20 commonly referred to as a step-and-scan apparatus — each target portion is irradiated by progressively scanning the mask pattern under the projection beam in a given reference direction (the "scanning" direction) while synchronously scanning the substrate table parallel or anti-parallel to this direction; since, in general, the projection system will have a magnification 25 factor M (generally  $< 1$ ), the speed V at which the substrate table is scanned will be a factor M times that at which the mask table is scanned. More information with regard to lithographic devices as here described can be gleaned, for example, from US 6,046,792, incorporated herein by reference.

In a manufacturing process using a lithographic projection apparatus, a 30 pattern (e.g. in a mask) is imaged onto a substrate that is at least partially

covered by a layer of radiation-sensitive material (resist). Prior to this imaging step, the substrate may undergo various procedures, such as priming, resist coating and a soft bake. After exposure, the substrate may be subjected to other procedures, such as a post-exposure bake (PEB), development, a hard 5 bake and measurement/inspection of the imaged features. This array of procedures is used as a basis to pattern an individual layer of a device, e.g. an IC. Such a patterned layer may then undergo various processes such as etching, ion-implantation (doping), metallization, oxidation, chemo-mechanical polishing, etc., all intended to finish off an individual layer. If several layers 10 are required, then the whole procedure, or a variant thereof, will have to be repeated for each new layer. Eventually, an array of devices will be present on the substrate (wafer). These devices are then separated from one another by a technique such as dicing or sawing, whence the individual devices can be mounted on a carrier, connected to pins, etc. Further information regarding 15 such processes can be obtained, for example, from the book "Microchip Fabrication: A Practical Guide to Semiconductor Processing", Third Edition, by Peter van Zant, McGraw Hill Publishing Co., 1997, ISBN 0-07-067250-4, incorporated herein by reference.

For the sake of simplicity, the projection system may hereinafter be 20 referred to as the "lens"; however, this term should be broadly interpreted as encompassing various types of projection system, including refractive optics, reflective optics, and catadioptric systems, for example. The radiation system may also include components operating according to any of these design types for directing, shaping or controlling the projection beam of radiation, and such 25 components may also be referred to below, collectively or singularly, as a "lens". Further, the lithographic apparatus may be of a type having two or more substrate tables (and/or two or more mask tables). In such "multiple stage" devices the additional tables may be used in parallel, or preparatory steps may be carried out on one or more tables while one or more other tables 30 are being used for exposures. Dual stage lithographic apparatus are described,

for example, in US 5,969,441 and WO 98/40791, both incorporated herein by reference.

The radiation system has to ensure the realization of a desired intensity distribution at the substrate as a function of position across the beam and as a function of angle of incidence of different rays in the beam. The desired position dependence, excluding mask generated patterns, generally has to be uniform with constant intensity as a function of position on the substrate, and the desired angle dependence has to peak at certain angles. The desired angle dependence may depend the nature of the pattern on the mask. Therefore it has to be possible to change the spatial properties of the illumination of the mask, so that the appropriate desired properties can be realized.

European Patent application EP 1109067, which is incorporated herein by way of reference, describes examples of such an illuminating system. The illuminating system has a laser source, followed by an optical element such as a Diffraction Optical Element (DOE) and a lens. The lens is followed by an optical sub-system that passes the beam to the mask. The optical sub-system uses a plane behind the DOE and the lens as a pupil plane for illuminating the mask. The pupil plane is in the focus of the optical sub-system, so that the position dependence of the intensity of the beam determines the angle dependence of intensity of the beam at the mask and the substrate ("angle" in this context may refer to the angle relative to the main direction of the beam, as well as to an angle rotated around that main direction). For the sake of completeness, it may be noted moreover that, although the position dependence, the optical sub-system overlays a number of different reflections of the beam onto the mask, so that in fact the angle dependence is determined by the overlap of a number of mirrored copies of the position dependence.

EP 1109067 uses the DOE to control the position dependence of the intensity distribution of the projection beam in the pupil plane, and thereby to control the angle dependence of the intensity distribution at the substrate. It is

described for example, how the function of an axicon (providing zero intensity in a circle in the centre of the pupil plane) can be implemented with a DOE.

Basically the DOE comprises an array of microlenses, each defining a region transverse to the direction of the beam, through which radiation from the beam is passed. Conventionally, the region of each microlens has a circular or hexagonal shape, which would lead to a circle or hexagonal shaped intensity distribution in the pupil plane. However, by using a different shapes, different distributions can be realized. For example, by using ring shaped microlenses, which pass radiation only through a ring in the microlens, a ring shaped intensity distribution can be realized in the pupil plane. Similarly, a dipole shaped region, with lobes that pass radiation emanating in mutually opposite directions from the centre of the lens, a dipole intensity distribution can be realized in the pupil plane. By using an array of identical microlenses across the beam inhomogeneity of the beam does not significantly affect the intensity distribution in the pupil plane.

Dependent on the particular integrated circuit topology under process, or even the particular process step, different position dependencies of the intensity distribution in the pupil plane may be needed. For this purpose EP 1109067 provides a DOE exchange unit, so that a DOE for creating a desired intensity distribution can be introduced into the beam as needed.

Since the DOE plays a crucial role in realizing the desired intensity distribution in the pupil plane, it is usually necessary to design DOE's specifically for different possible desired intensity distributions and to change the DOE, dependent on the desired distribution. However, if a specific DOE must be designed and made for each possible desired intensity distribution, a considerable delay for designing and manufacturing the DOE results each time a new intensity distribution is needed. Also a very large number of DOE's is needed in this way.

EP 1109067 also describes various ways to place a number of different DOE's in parallel in the incoming beam. Each DOE creates a part of the beam

with, so that the intensity at the pupil plane is a sum of contributes from different DOE's. New intensity distributions can be generated by using different combinations of DOE's without manufacturing new DOE's.

Of course this requires a homogeneous distribution of the incoming beam over the various DOE's. Thus, one of the main advantages of using DOE's is sacrificed to a certain extent: the fact that an array of microlenses with identical effect is used in parallel, so that inhomogeneity of the beam does not matter. To alleviate this inhomogeneity a large number of parallel Doe's is required, assembled at random over the beam area. This makes assembly and re-use complicated.

Furthermore EP 1109067 describes serial placement of different DOE's in the path of the beam. For example, one DOE generates a ring-shaped pupil (which is normally done by an axicon) while another (serially placed) DOE generates a filled, circular pupil (which is normally done by the zoom-optics). Usually these pupil shapes exclude each other: from a single DOE only a ring and a filled circular pupil can be made, not both. The effect of serial placement is to convolute the position dependences imparted by the various DOE's to the intensity distribution in the pupil plane. Convolution of a first and second intensity pattern has the effect of spreading each point of the first intensity pattern with a distribution determined by the second pattern. Thus convolution can be used for example to widen a ring in a pattern where the intensity is limited to a ring shaped region in the pupil plane. However, convolution generally does not provide refined control over the intensity distribution in particular when a number of DOE's are placed in series. Accordingly, EP 1109067 uses the convolution of different DOE's in serial placement for specific purposes, like the above mentioned broadening of the ringwidth. Another example is that one DOE generates a circular pupil which due to different optical losses in the x- and y-direction gets non-circular (e.g. elliptical) at reticle level. This might lead to different widths of horizontal as compared to vertical lines on the wafer. The ellipticity can be compensated by

serially inserting a second DOE which radiates preferably in one direction, the convolution of which with the first DOE gives the wanted circular pupil at reticle level.

However, for other types of composition convolution is less suitable.

5 Thus specific new angle dependences of the intensity distribution in the pupil plane, for example, generally still require parallel arrangement or manufacture new DOE's.

It is an object of the present invention to provide for a lithographic 10 apparatus in which the intensity distribution in the pupil plane can be composed additively without relying on homogeneity of the beam.

It is a further object to control the intensity as a function of the angle of rotation around a centre of the pupil plane in this way.

It is another object of the present invention to provide for a lithographic 15 apparatus in which more control is afforded over the intensity distribution in the pupil plane when DOE's are placed in series.

This and other objects are achieved according to the invention in a lithographic apparatus as specified in the opening paragraph, characterized by the characterizing part of Claim 1.

20 According to the invention an intensity distribution in the pupil plane is composed by serial arrangement of a number of optical elements each for deflecting the beam over a range of directions with a direction dependent intensity distribution. The optical elements have been designed so that each passes a major part of the beam without deflection, only a minor part being 25 deflected with a direction dependent intensity distribution specific to the optical element. By a major part of the passed intensity is meant more than half of the beam power of the beam that has passed the optical element. Preferably, even more than 80% or even 90% or 98% of the beam power that is passed is passed undeflected. The part of the beam that is passed undeflected 30 by all optical elements is blocked out before it reaches the substrate. As a

result the intensity distribution in the pupil plane is approximately a summation of the patterns imparted by the individual optical elements.

In an embodiment, the optical elements include at least one and preferably at least two optical elements that by themselves would induce an 5 intensity distribution in the pupil plane, so that the pattern varies as a function of the rotation angle around the main beam direction. By combining such optical elements various rotation angle dependent patterns can be composed.

Preferably, each optical element in the series arrangement comprises an 10 array of microlenses that are all designed to provide the desired pattern of intensity in the pupil defined by that optical element plus an undeflected part of the beam. Thus, the optical element is spatially homogeneous across the beam, and insensitive for inhomogeneity of the beam. Fine grain interspersed with the microlenses "flat" optical parts may be included in the array 15 (preferably in each unit cell of the array) to pass the major part of the beam undeflected.

In one embodiment, the microlenses are designed as diffractive optical elements, by introducing steps of a fixed size in the thickness of the microlenses so as to restrict the range of thickness values of the microlenses. 20 Conventionally, the step size is equal to an integer number of wavelengths of radiation from the (monochromatic) radiation source, since such a step does results in optimal efficiency. According to the invention microlenses are used that have been designed for a wavelength that differs from the wavelength of the beam, i.e. so that the wavelength of the beam differs from the wavelength 25 for which the microlenses are optimally efficient. This difference from the optimal wavelength is taken so large that the major part of the projection beam is passed undeflected.

Preferably the intensity in each of a number of respective ranges of the pupil plane is controlled mainly by a respective one of the optical element that have 30 been placed in series. Thus, different optical elements may be used of which

each controls the rotation angle dependence of the intensity in a respective ring in the pupil plane (or at least is more determinative of the intensity in that ring than other ones of the optical elements). Preferably, the optical elements are rotated to a selectable angle so as to control an offset of the 5 rotation angle dependence in the pupil plane. Instead of in ring shaped ranges, the optical element may control the intensity distribution in ranges of other shapes, e.g. in rectangular "pixels" in the pupil plane. Preferably, a set of optical elements is provided for each range, so that the intensity distribution in each range of the pupil plane can be selected substantially independently 10 from that in other ranges.

Although specific reference may be made in this text to the use of the apparatus according to the invention in the manufacture of ICs, it should be explicitly understood that such an apparatus has many other possible 15 applications. For example, it may be employed in the manufacture of integrated optical systems, guidance and detection patterns for magnetic domain memories, liquid-crystal display panels, thin-film magnetic heads, etc. The skilled artisan will appreciate that, in the context of such alternative 20 applications, any use of the terms "reticle", "wafer" or "die" in this text should be considered as being replaced by the more general terms "mask", "substrate" and "target portion", respectively.

In the present document, the terms "radiation" and "beam" are used to encompass all types of electromagnetic radiation, including ultraviolet (UV) 25 radiation (e.g. with a wavelength of 365, 248, 193, 157 or 126 nm) and extreme ultra-violet (EUV) radiation (e.g. having a wavelength in the range 5-20 nm), as well as particle beams, such as ion beams or electron beams.

Embodiments of the invention will now be described, by way of example only, with reference to the accompanying schematic drawings in which corresponding reference symbols indicate corresponding parts, and in which: 30 - Figure 1 depicts a lithographic projection apparatus according to an

embodiment of the invention;

- Figure 2 shows an optical path
- Figure 3 illustrates directions relative to a main beam direction
- Figure 4 shows an array of microlenses
- 5 Figure 5 shows a series of partial cross-sections of microlenses
- Figure 6 shows a series of rings in the pupil plane

Figure 1 schematically depicts a lithographic projection apparatus 1 according to a particular embodiment of the invention. The apparatus comprises:

- 10 - a radiation system Ex, IL, for supplying a projection beam PB of radiation (e.g. UV radiation). In this particular case, the radiation system also comprises a radiation source LA;
- a first object table (mask table) MT provided with a mask holder for holding a mask MA (e.g. a reticle), and connected to first positioning means PM for accurately positioning the mask with respect to item PL;
- 15 - a second object table (substrate table) WT provided with a substrate holder for holding a substrate W (e.g. a resist-coated silicon wafer), and connected to second positioning means PW for accurately positioning the substrate with respect to item PL; and
- 20 - a projection system ("lens") PL for imaging an irradiated portion of the mask MA onto a target portion C (e.g. comprising one or more dies) of the substrate W.

As here depicted, the apparatus is of a transmissive type (i.e. has a transmissive mask). However, in general, it may also be of a reflective type, for 25 example (with a reflective mask). Alternatively, the apparatus may employ another kind of patterning means, such as a programmable mirror array of a type as referred to above.

The source LA (e.g. a laser) produces a beam of radiation. This beam is fed into an illumination system (illuminator) IL, either directly or after having 30 traversed conditioning means, such as a beam expander Ex, for example. The

illuminator IL may comprise adjusting means AM for setting the outer and/or inner radial extent (commonly referred to as  $\sigma$ -outer and  $\sigma$ -inner, respectively) of the intensity distribution in the beam. In addition, it will generally comprise various other components, such as an integrator IN and a condenser CO. In 5 this way, the beam PB impinging on the mask MA has a desired uniformity and intensity distribution in its cross-section.

It should be noted with regard to figure 1 that the source LA may be within the housing of the lithographic projection apparatus (as is often the case when the source LA is a mercury lamp, for example), but that it may also 10 be remote from the lithographic projection apparatus, the radiation beam which it produces being led into the apparatus (e.g. with the aid of suitable directing mirrors); this latter scenario is often the case when the source LA is an excimer laser. The current invention and claims encompass both of these scenarios.

15 The beam PB subsequently intercepts the mask MA, which is held on a mask table MT. Having traversed the mask MA, the beam PB passes through the lens PL, which focuses the beam PB onto a target portion C of the substrate W. With the aid of the second positioning means PW (and interferometric measuring means IF), the substrate table WT can be moved accurately, e.g. so as to position different target portions C in the path of the beam PB. Similarly, the first positioning means PM can be used to accurately 20 position the mask MA with respect to the path of the beam PB, e.g. after mechanical retrieval of the mask MA from a mask library, or during a scan. In general, movement of the object tables MT, WT will be realized with the aid of 25 a long-stroke module (coarse positioning) and a short-stroke module (fine positioning), which are not explicitly depicted in figure 1. However, in the case of a wafer stepper (as opposed to a step-and-scan apparatus) the mask table MT may just be connected to a short stroke actuator, or may be fixed. Mask MA and substrate W may be aligned using mask alignment marks M1, M2 and 30 substrate alignment marks P1, P2.

The depicted apparatus can be used in two different modes:

1. In step mode, the mask table MT is kept essentially stationary, and an entire mask image is projected in one go (i.e. a single "flash") onto a target portion C. The substrate table WT is then shifted in the x and/or y directions so that a different target portion C can be irradiated by the beam PB; and
2. In scan mode, essentially the same scenario applies, except that a given target portion C is not exposed in a single "flash". Instead, the mask table MT is movable in a given direction (the so-called "scan direction", e.g. the y direction) with a speed  $v$ , so that the projection beam PB is caused to scan over a mask image; concurrently, the substrate table WT is simultaneously moved in the same or opposite direction at a speed  $V = Mv$ , in which M is the magnification of the lens PL (typically,  $M = 1/4$  or  $1/5$ ). In this manner, a relatively large target portion C can be exposed, without having to compromise on resolution.

Figure 2 shows a more detailed schematic view of an embodiment of the optical path of the lithographic apparatus, including the illumination system. Beam PB is indicated by a dashed line. Beam PB passes from radiation source LA through an angular dependence shaping unit 12, a rod 16, condenser optics 18, mask MA, projection lens PL onto substrate W. Here and in the following the word "lens" should be understood as a general term, referring not just to a single piece of optically shaped glass, but more generally including various types of optically active systems, including refractive optics, reflective optics, and catadioptric systems, composed of a single element or of a combination of elements. Furthermore, it should be understood that, although a straight optical path is shown for the sake of simplicity, without deviating from the invention various mirrors may be included into the optical path so as to introduce angles into the optical path in practice.

Angular dependence shaping unit 12 contains a series arrangement of DOE's 120a-b (Diffractive Optical Elements) in the path of projection beam PB. By way of example, two such DOE's 120a-b have been shown in series, but it

should be appreciated that a greater number of such elements may be used in series. The series arrangement of DOE's is followed by a zoom lens 124, a blocking element 125, an axicon 122, and a coupling lens 126 in the path of beam PB. The optical path defines a pupil plane 14 for illuminating mask MA.

5 Pupil plane is in a focal plane of the optics that pass beam PB onto mask MA. Pupil plane 14 lies between zoom lens 124 and coupling lens 126. A DOE exchange unit 24 is provided, implemented for example as a pair of carousels for exchanging DOE's 120a,b with different DOE's from the exchange unit 24.

In operation angular dependence shaping unit 12 controls a position 10 dependence of the intensity of beam PB in pupil plane 14. The position dependence in turn determines the way the intensity of the beam at mask MA depends on the angle of incidence. In this context, the word "angle" refers to directions relative to a main direction of beam PB.

Figure 3 illustrates directions in terms of two angle values Theta and 15 Phi. Theta represents an angle of deflection of a direction 30 of radiation from the main direction 32 of beam PB and Phi represents an angle of rotation around the main direction 32 of the beam from a reference direction 34.

For semi-conductor processing purposes, among others, it is desirable to be able to control the intensity distribution of beam PB as a function of Theta 20 and Phi at patterning means MA and thereby at substrate W. Axicon 122 and zoom lens 124 serve to select an adjustable ring, i.e. a range of Theta values to which the intensity is limited at substrate W. This corresponds to intensity limited to a ring of positions in pupil plane 14. DOE's 120a,b are used to select at least the Phi dependence, to provide for example a dipole shaped pattern, 25 wherein the intensity is concentrated in a range of phi values between plus and minus 45 degrees and between 135 and 225 degrees for example. This corresponds to intensity limited to lobes op positions in these directions in pupil plane 14.

The series arrangement of two DOE's 120a,b is provided for composing 30 desired angle dependent intensity distributions for illuminating substrate W.

Each DOE 120a,b is designed to pass beam PB mainly unaffected, breaking the direction of a part of the radiation in the beam with a predetermined angle dependence. Beam PB reaches first DOE 120a mainly collinearly so that a first part of beam is deflected over a first range of directions determined by first

5 DOE 120a. Most of beam PB passes first DOE 120a collinearly and reaches second DOE 120b where a second part of beam PB is deflected over a second range of directions determined by second DOE 120b. Most of the first part is passed unaffected by second DOE 120b. A minor further part of the first part is again redirected. As a result, beam PB leaves the series arrangement of

10 DOE's partly unaffected and partly deflected: a first part deflected over a first range determined by first DOE 120a, a second part deflected over a second range determined by second DOE 120b and a further part deflected twice.

Axicon 122 pushes the direction of radiation that has been passed by DOE's 120a, b outward over an adjustable angle, so that a ring of directions remains. Zoom lens 124 scales adjustably the ring and images it onto pupil plane 14. Blocking element 125 blocks the undeflected part of beam PB. As a result the intensity as a function of position in pupil plane 14 is a sum of the first part and the second part of the beam PB that have been deflected by the first and second DOE 120a,b respectively and the further part, but the latter is

15 only a minor part.

20 Thus, by selecting different combinations of first and second DOE 120a,b different intensity distributions can be composed at pupil plane. For example the apparatus may be provided with a set of DOE's for each of a number of rings in the pupil plane. Figure 6 illustrates such a series of rings 25 60a-d, including a central disk in the pupil plane. Preferably, a set of one or more DOE's (or other optical elements) is provided for each ring 60a-d, respective ones of the DOE's (or other optical elements) of the set for a particular ring 60a-d defining respective intensity distributions limited to the particular ring 60a-d, each for example having intensity only over its own 30 range of angles around the centre of the rings (e.g. one DOE with intensity

from 0-22.5 degrees, 90-112.5 degrees, 180-202.5 degrees and 270-290.5 degrees, and others with different ranges). It will be appreciated that, without deviating from the invention, the optical elements of one set may contribute some intensity in the range of another set, but the optical elements of each set 5 contribute more to the position dependence in its range than the optical elements of the other sets. By selecting a DOE for each of the rings and placing the DOE's selected for different rings in series a desired pattern can be composed. Optionally, moreover, each DOE may be rotated to rotate the selected ranges.

10 Obviously, other sets of DOE's may be used, for example each with respective intensity distributions for a different row or columns in pupil plane 14. Or a set of DOE's each providing intensity in a respective region in a grid of regions in pupil plane 14.

15 It is also possible to place DOE's in series that provide intensity in overlapping regions in pupil plane 14. Thus, an intensity pattern may be realized that assumes more than one value in addition to zero intensity.

DOE's 120a,b are preferably arranged as an array of microlenses each 20 with the same shape in a plane perpendicular to the main beam direction. Figure 4 shows part of such an array of microlenses 40a-j for a dipole shape. All microlenses 40a-j have the dipole shape around an optical centre (marked with a cross 42). Of course the dipole shape of figure 4 is only an example. In another ring segment shaped elements may be used. Exactly at the optical centre 42 beam PB is passed without deflection. At increasing distances from optical centre 42 beam PB is increasingly deflected, typically toward the 25 central axis of the microlens 40a-j, so that all rays converge at a common focus. The dipole shape radiation from beam PB is deflected more than a minimum amount by each lens only in selected directions in a range of rotation from 90 to 120 degrees around the beam and in a range of 270 to 300 degrees. This results in intensity concentrated in a corresponding range of locations in pupil 30 plane 14. In order minimize divergence of the part that is deflected less than

the minimum the central part of each microlens may be manufactured with constant thickness. In this case all intensity due to the circular central part is substantially concentrated in one point of pupil plane 14, from which it is blocked out.

5       DOE's are generally realized starting from a desired thickness profile  $d(r)$  as a function of position  $r$  in the plane of the lens. However, it is desirable to restrict the range of thickness variation. For this purpose, it has been known to make the thickness  $d'(r)$  of the DOE vary as a function of position  $r$  approximately as this thickness  $d(r)$  modulo a basic thickness  $d_0$  related to the

10      wavelength of the radiation in beam PB, that is, to obtain  $d'(r)$  by subtracting a position  $r$  dependent integer number of basic thicknesses  $d_0$  from  $d(r)$ , so that  $d'$  remains within a limited range (in this case a range of one basic thickness  $d_0$ ). Thus, when  $d(r)$  increases continuously,  $d'(r)$  drops back by one basic thickness each time  $d(r)$  crosses an integer number of basic thicknesses.

15      Preferably, to obtain optimal efficiency, the basic thickness  $d_0$  is chosen so that the diffraction grating effect caused by the drops in thicknesses leads to constructive interference in the direction in which the sloping  $d(r)$  refracts the radiation. For small slopes of  $d(r)$   $d_0$  may be chosen substantially equal to the wavelength of the radiation.

20      It should be realized that the essential point of such DOE's is that the thickness steps related to an integer number of wavelengths are used to counteract a continuous rise or fall of the thickness, in order to keep the thickness within some desired range. Use of wavelength related steps and restriction of steps to positions  $r$  where  $d(r)$  assumes values from a set of

25      values that are an integer number of basic thickness values apart ensure a minimum range of thickness variations, but is not essential. In different embodiments any integer number of basic thickness values may be used in the steps, so that  $d'(r)$  drops back by any number of basic thickness values. Also the drops may occur anywhere. This does not significantly affect the operation

30      of the lens.

When designed with steps that chosen for optimal efficiency for the wavelength of (substantially monochromatic) radiation source LA, however, such a DOE is of no use for the invention, because it doe not pass a major part of the beam unaffected. In this case putting several such DOE's in series 5 results in convolution of the position dependences of the intensity in pupil plane 14 that would be imparted by the individual DOE's and not in addition of these position dependencies.

In the DOE's 120a,b for use in the invention, preferably DOE's designed for a different wavelength than the wavelength of the (monochromatic) 10 radiation of beam PB is used. The efficiency of the DOE, more in particular the ratio between the intensity of radiation that is deflected in the proper direction for lens effects and the intensity of undeflected radiation, attains a maximum for an optimal basic thickness step. A lower efficiency occurs when a thickness step substantially smaller or higher than the wavelength is made each time to 15 check a continuous rise or drop of the thickness. With such a "wrong" thickness step DOE's 120a,b work only partly as lenses, and pass the major part of beam PB essentially unaffected. This makes it possible to obtain the sum of the effect of successive DOE's 120a,b in the serial arrangement. A 'wrong' wavelength of 633 nm (e.g.a red laser-pointer) already gives a satisfactory level 20 of unaffected transmission for 193nm DOE's. Of course, this effect is not limited to steps that are smaller than the wavelength. One may also use larger steps.

It should be realized however that, although use of such DOE's designed for smaller wavelengths is preferred, partly passing beam PB unaffected and 25 partly deflecting beam PB may be realized in different ways. For example, an array of microlenses may be used, wherein a constant optical thickness part is included in each microlens, which covers a major part of the microlens for example in the middle of the microlens. Alternatively, constant thickness element may be included in the array of microlenses, interspersed with the 30 microlenses.

Without deviating from the invention it is possible to use an array of microlenses that pass a major part of beam PB through a central area, which deflects the radiation less than a threshold level, a minor part of beam PB being deflected more, in an angle dependent pattern (for example according to a dipole pattern). In the series arrangement 120a,b the small deflection of the major part by the first DOE 120a leads to an amount of widening of the pattern created by the second DOE 120b, but this is acceptable as long as it remains below a threshold. In this embodiment the combination of DOE's passes a widened central part of beam PB to pupil plane 14, which increases with the threshold.

In this case, passing a major part of beam PB is realized by using a corresponding major part of the area of the lens in the centre of the lens. This requires blocking an increasingly larger area of pupil plane when the major part is increased. This makes it impossible to provide intensity in a central area of pupil plane 14. To reduce this "excluded" area it is desirable that the major part of beam PB is passed deflected to a minimum extent, preferably less than the amount of deflection obtained by using a correspondingly major part of the area of the lens. This is realized for example by using a constant thickness area in a major part of the lens area, or by interspersing constant thickness regions between the microlenses (preferably in each unit cell of the array of microlenses) or by using a DOE designed for a smaller wavelength than the wavelength of radiation source LA.

Furthermore, preferably arrays of microlenses are used wherein a continuously varying thickness is approximated by discrete thickness steps, for example of a fraction of the maximum thickness step. Herein, a continuously changing profile is approximated by a staircase thickness profile with steps that are typically a fraction of the maximum thickness step, the staircase dropping back an maximum thickness step at some positions so as to limit the number of discrete thickness levels. Such a profile can be conveniently manufactured using photolithographic process steps that are familiar from

semi-conductor manufacturing techniques. Designed for the "wrong" wavelength it may be used to obtain addition of position dependencies in pupil plane 14.

Figure 5 shows a series of partial cross-sections of different microlenses 5 50a-c, with a continuous thickness profile 52, a modulo thickness profile 54 with steps with size h that restrict the range of thickness values of the microlens, and a quantized thickness profile 56 with thickness variation implemented using a series of discrete levels respectively. Preferably the step size h in the microlenses used in DOE's 120a,b is smaller than the wavelength 10 of radiation source LA.

Whilst specific embodiments of the invention have been described above, it will be appreciated that the invention may be practiced otherwise than as described. The description is not intended to limit the invention. For example, a greater number of DOE's than the two DOE's 120a,b may be used in series to 15 provide for more detailed control over the intensity distribution in pupil plane 14. As another example, although an axicon 122 and a zoom lens 124 have been shown, the function of any of these elements may of course be implemented by means of DOE's.

Furthermore, although blocking element 125 has been shown positioned 20 in front of axicon 122, blocking element may in fact be included at any convenient location in or near any pupil plane, provided that blocking element blocks out radiation that has passed the series arrangement of DOE's 120a-b undeflected, before it reaches the substrate. In principle the diameter of blocking element 125 may be very small, particularly if the blocking element is 25 located exactly in a pupil plane since it needs to block out radiation in only one point of the pupil plane, plus a surrounding corresponding to tolerances for unintended deflection errors. However, when a central part of a lens is used to pass the beam deflected less than a threshold, a correspondingly larger diameter should be used for blocking element 125.

Claims

1. A lithographic projection apparatus comprising:
  - a radiation system for providing a projection beam of radiation, the radiation system defining an intensity distribution in a pupil plane, the radiation system comprising an optical element for deflecting the projection beam over a range of directions with a direction dependent intensity distribution determined by the optical element;
  - a support structure for supporting patterning means, the patterning means serving to pattern the projection beam received from the pupil plane according to a desired pattern;
- 10 - a substrate table for holding a substrate; and
  - a projection system for projecting the patterned beam onto a target portion of the substrate, characterized in that the apparatus comprises
    - a further optical element following said optical element in a path of the projection beam, the optical element and the further optical element each being arranged to pass a major part of passed intensity of the projection beam substantially without deflection, the further optical element deflecting the major part passed by the optical element over a further range of directions with a direction dependent intensity distribution;
- 15 - a blocking element for blocking transmission to the substrate of the part of intensity of the projection beam passed undeflected by both the optical element and the further optical element.
- 20 2. A lithographic projection apparatus according to Claim 1, comprising a plurality of further optical elements, including the further optical element, successively following said optical element in the path of the projection beam, each further optical elements passing a major part of passed intensity of the projection beam substantially without deflection, and each providing for

deflection of the major part of passed intensity of the projection beam received from the preceding optical elements over a respective range of directions with a respective further direction dependent intensity distribution.

3. A lithographic projection apparatus according to Claim 1 or 2, wherein the optical element and the further optical element provide both for mutually different direction dependent intensity distributions, as a function of an angle of the direction rotating around the normal beam direction.
4. A lithographic projection apparatus according to Claim 3, wherein the optical element provides for an intensity distribution with substantially either a first intensity level as a function direction rotating around the normal beam direction or substantially no intensity, the further optical element providing for an intensity distribution with substantially either a second intensity level different from the first intensity level as a function of direction rotating around the normal beam direction or substantially no intensity.
5. A lithographic projection apparatus according to any one of the preceding Claims, wherein each of the optical elements contains an array of microlenses across a cross-section of the beam.
6. A lithographic projection apparatus according to Claim 5, wherein the radiation source is substantially monochromatic with a first wavelength, the microlenses each including thickness steps so as to keep a range of thickness values of the microlenses within a predetermined range and to optimize efficiency of the microlenses at a second wavelength, the first wavelength differing from the second wavelength to an extent so that the efficiency at the first wavelength is so low that the major part of the passed intensity of the projection beam is passed undeflected.
7. A lithographic projection apparatus according to any one of the preceding Claims, comprising an optical element exchange unit, with positions for a plurality of available optical elements, each providing for a respective direction dependent intensity distribution, the optical element exchange unit being arranged for moving selected ones of the available optical elements to a

position following said optical element to function as said further optical element.

8. A lithographic projection apparatus according to Claim 7, comprising a plurality of respective sets of optical elements, each respective set containing one or more optical elements that determine the intensity in the pupil plane in a respective range of positions specific to the respective set, the exchanging unit being arranged to place independently selectable ones of the optical elements of the respective sets into successively different positions in the series arrangement of optical element.  
5
- 10 9. A device manufacturing method comprising the steps of:
  - providing a substrate that is at least partially covered by a layer of radiation-sensitive material;
  - providing a projection beam of radiation using a radiation system;
  - passing the projection beam through an optical element for deflecting the beam over a range of directions with a direction dependent intensity distribution determined by the optical element;
  - using patterning means to endow the projection beam with a pattern in its cross-section; and
  - projecting the patterned beam of radiation onto a target portion of the 15 layer of radiation-sensitive material,20 characterized by
  - passing the projection beam through a further optical element following said optical element in a path of the projection beam, the optical element and the further optical element each being arranged to pass a major part of the passed 25 intensity of the projection beam substantially without deflection, the further optical element deflecting the major part of the intensity passed by the optical element over a further range of directions with a direction dependent intensity distribution;

- blocking transmission to the substrate of the part of the projection beam passed undeflected by both the optical element and the further optical element.

10. A device manufacturing method according to Claim 9, comprising  
5 passing the projection beam through a plurality of further optical elements, including the further optical element, successively following said optical element in the path of the projection beam, each further optical element passing a major part of the passed intensity of the projection beam substantially without deflection, and each providing for deflection of the major  
10 part of the passed intensity of the projection beam received from the preceding optical elements over a respective range of directions with a respective further direction dependent intensity distribution.

11. A device manufacturing method according to Claim 9 or 10, wherein the optical element and the further optical element provide both for mutually  
15 different direction dependent intensity distributions, as a function of an angle of the direction rotating around the normal beam direction.

12. A device manufacturing method according to Claim 11, wherein the optical element provides for an intensity distribution with substantially either a first intensity level as a function direction rotating around the normal beam  
20 direction or substantially no intensity, the further optical element providing for an intensity distribution with substantially either a second intensity level different from the first intensity level as a function of direction rotating around the normal beam direction or substantially no intensity.

13. A lithographic projection apparatus according to any one of Claims 9-12,  
25 wherein each of the optical elements contains an array of microlenses across a cross-section of the beam.

14. A device manufacturing method according to claim 13, wherein the radiation is substantially monochromatic with a first wavelength, the microlenses each including thickness steps so as to keep a range of thickness  
30 values of the microlenses within a predetermined range and to optimize

efficiency of the microlenses at a second wavelength, the first wavelength differing from a second wavelength to an extent so that the efficiency at the first wavelength is so low that the major part of the passed intensity of the projection beam is passed undeflected.

- 5 15. A device manufacturing method according to any one of claims 9 to 14, comprising providing a plurality of respective sets of optical elements, each respective set containing one or more optical elements that determine the intensity in the pupil plane in a respective range of positions specific to the respective set, selecting a series of optical elements, each from a respective one  
10 of the sets and placing the selected optical elements in series in the projection beam.
16. A device manufacturing method according to any one of Claims 9 to 14, wherein the optical element and the further optical element are part of a series of optical elements that each pass a majority of the passed projection beam  
15 undeflected, each optical element of the series determining a rotation angle dependent intensity distribution in a respective ring around a centre of the pupil plane, more than other optical elements of the series.
17. A device manufacturing method according to Claims 16, the method comprising rotating the optical elements of the series so as to rotate the  
20 rotation angle dependent intensity distribution in the respective rings for the optical elements.

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Title: Lithographic Apparatus, Device Manufacturing Method, and Device Manufactured Thereby.

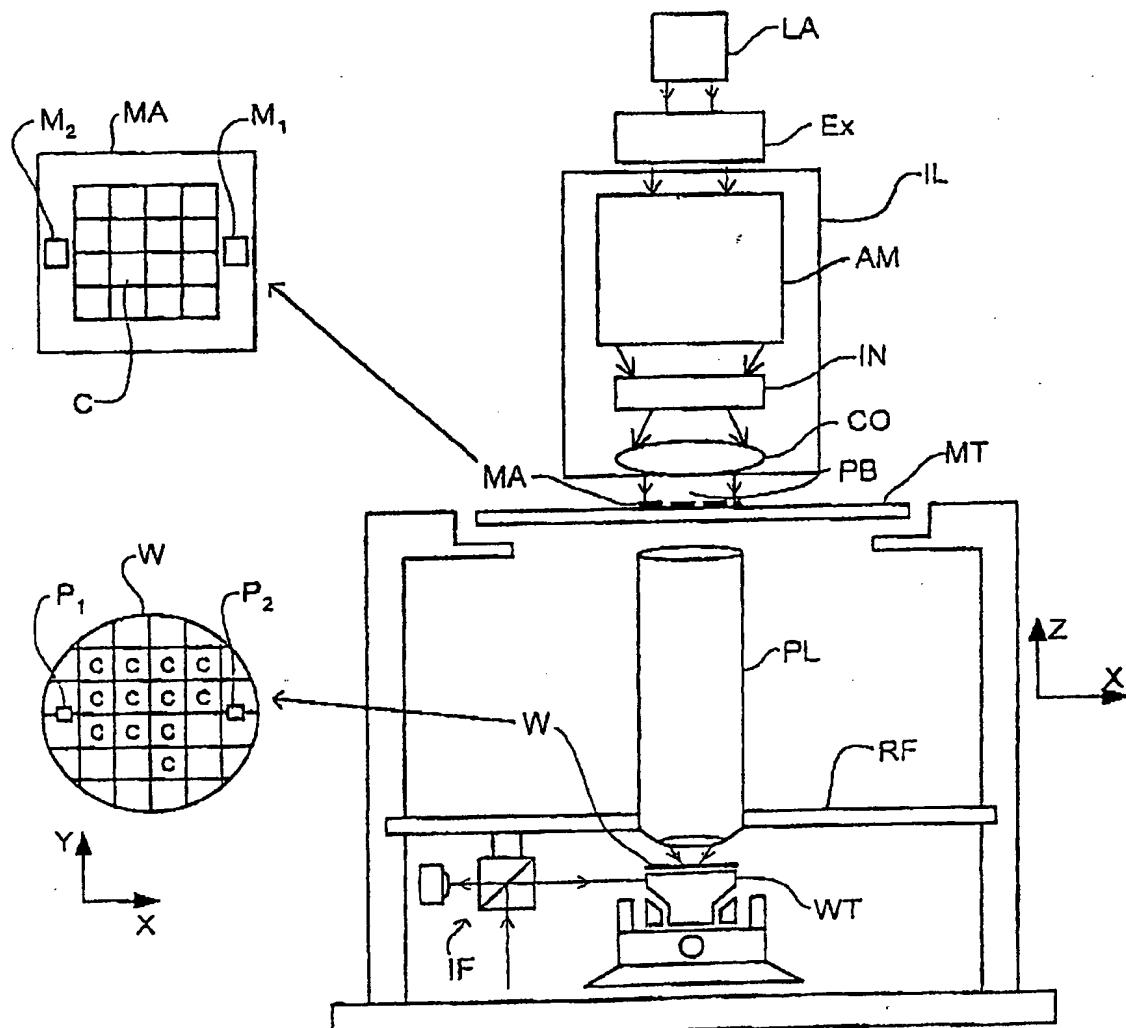
Abstract

A beam PB is projected onto a substrate W via a mask MA. The direction dependence of the intensity of the beam at the substrate W is controlled by passing the beam through a series of optical elements 120a-b in front of a pupil plane 14. The intensity distribution as a function of position in the pupil plane 14 determines the angle dependence at the substrate W. The optical elements 120a-b, which are preferably arrays of microlenses (or more particularly DOE's: Diffractive Optical Elements) each define an angle dependence of the intensity of the beam PB. The optical elements 120a-b are each arranged to pass a major part of the beam PB substantially without deflection and a minor part with deflection angle dependent intensity. The major part of the beam is blocked out of the beam behind the series of optical elements 120a-b. As a result an addition of the effects of upon the intensity in the pupil plane 14 is realized.

Fig. 2

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Fig.1.



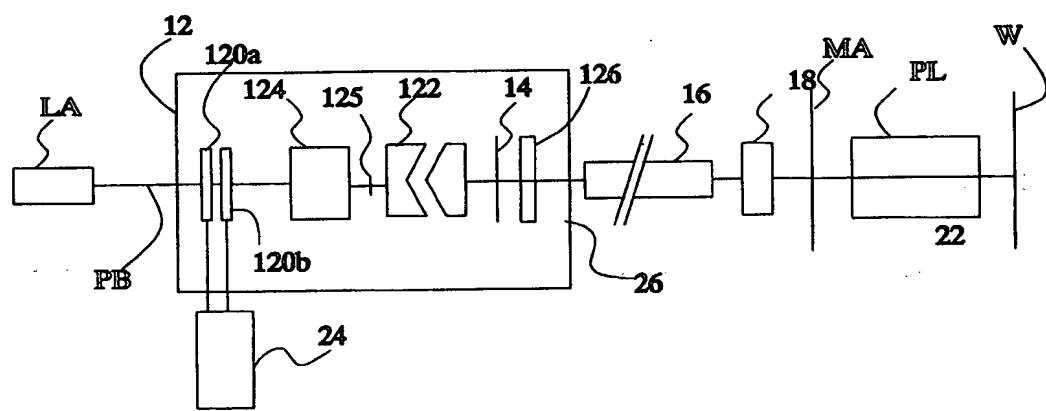


Fig. 2

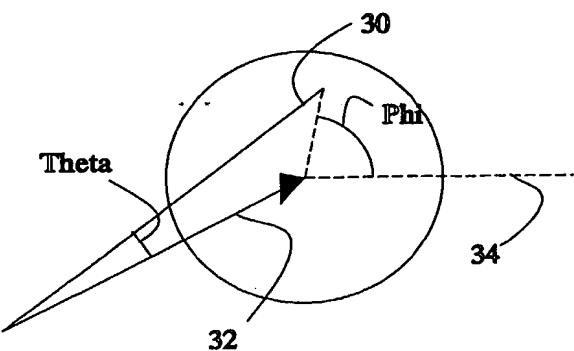


Fig. 3

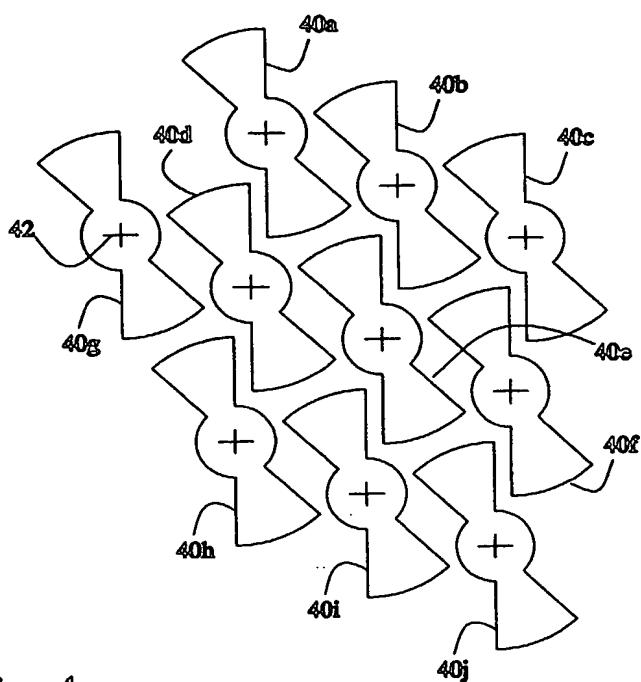


Fig. 4

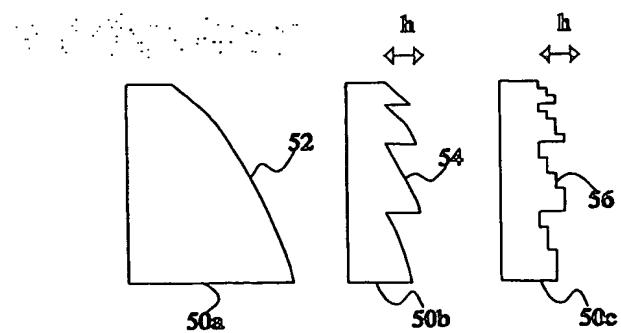


Fig. 5

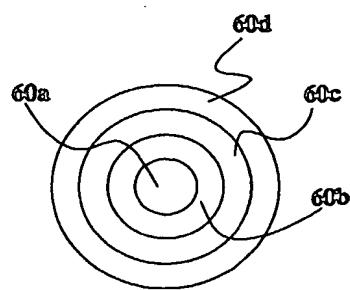


Fig. 6

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